

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|---|------------------|---------|------------------|
| L1 | 5 | ((mask near2 (memory or rom)) and gate and polysilicon and implant\$5 and buried and silicide and etch\$3). clm. | US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB | OR | ON | 2005/09/18 21:16 |